## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Koichi WATANABE et al.

Title:

SPUTTERING TARGET AND PROCESS FOR PRODUCING Si

OXIDE FILM THEREWITH

Appl. No.:

10/573,406

International

9/22/2004

Filing Date:

371(c) Date:

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Examiner:

Jason Berman

Art Unit:

1724

Confirmation 2973

Number:

## LETTER REGARDING SUPPLEMENTAL NOTICE OF ALLOWABILITY

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Applicants note that claim 13 is not shown correctly in the Supplemental Notice of Allowability and should read as:

13. The process for producing an Si oxide film according to claim 12, wherein the Si oxide

film is an optical thin film.

Respectfully submitted.

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FOLEY & LARDNER LLP

Customer Number: 22428 Telephone:

Facsimile:

(202) 945-6162 (202) 672-5399

Pavan K. Agarwal Attorney for Applicant Registration No. 40,888